

**KR1084239A: MONOLITHIC FLUIDIC NOZZLE ASSEMBLY BY USING
MONO-CRYSTALLINE SILICON WAFER AND PRODUCING METHOD
THEREOF**

Derwent Title: Manufacture of monolithic nozzle assembly for ink jet recording head involves depositing mask over substrate, forming aperture in portion of mask, and etching portion of substrate exposed through aperture to form a damper [\[Derwent Record\]](#)

Country: KR Republic of Korea
Kind: A Examined Patent Application ¹



[High Resolution](#)

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Published / Filed: 2001-09-06 / 2000-02-24

Application Number: KR2000000009103

IPC Code: B81C 1/00;

ECLA Code: None

Priority Number: 2000-02-24 **KR2000000009103**

INPADOC Legal Status: None **Buy Now:** [Family Legal Status Report](#)



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Family:

Other Abstract Info:

Buy PDF	Publication	Pub. Date	Filed	Title
<input checked="" type="checkbox"/>	US20010028378A1	2001-10-11	2001-02-23	Monolithic nozzle assembly formed with mono-crystalline silicon wafer and method for manufacturing the same
<input checked="" type="checkbox"/>	US6663231	2003-12-16	2001-02-23	Monolithic nozzle assembly formed with mono-crystalline silicon wafer and method for manufacturing the same
<input checked="" type="checkbox"/>	KR1084239A	2001-09-06	2000-02-24	MONOLITHIC FLUIDIC NOZZLE ASSEMBLY BY USING MONO-CRYSTALLINE SILICON WAFER AND PRODUCING METHOD THEREOF
<input checked="" type="checkbox"/>	JP2001287369A2	2001-10-16	2001-02-23	INTEGRAL FLUID NOZZLE ASSEMBLY UTILIZING SINGLE CRYSTAL SILICON WAFER AND ITS FABRICATION METHOD
4 family members shown above				

None

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